



(51) International Patent Classification:
H01J 3/40 (2006.01) *H05H 7/00* (2006.01)
C23C 4/00 (2006.01)

(21) International Application Number:
PCT/SG2011/000342

(22) International Filing Date:
30 September 2011 (30.09.2011)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
1016501.7 1 October 2010 (01.10.2010) GB

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(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

[Continued on next page]

(54) Title: FILTER FOR REMOVING MACRO-PARTICLES FROM A PLASMA BEAM

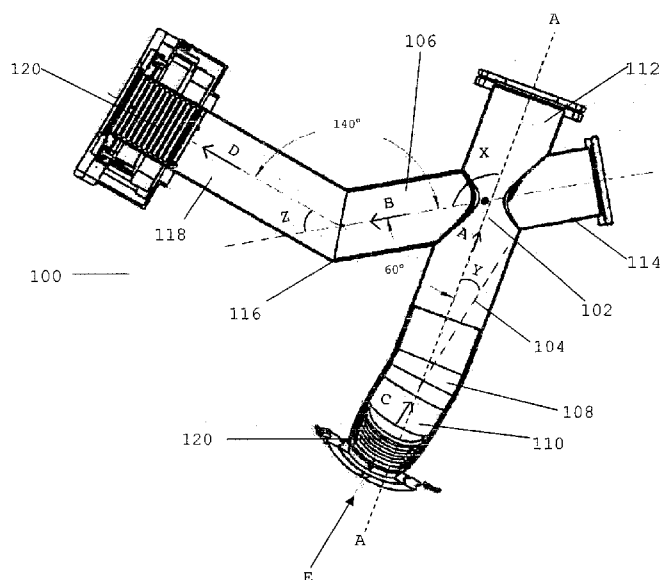


FIG. 1A

(57) Abstract: A filter for filtering macro-particles from a plasma beam, the filter comprising a bend-ed duct for carriage of said plasma beam, the bend-ed duct comprising an intermediate portion con-nected at one end to an inlet portion having a lon-gitudinal axis disposed on an inlet plane and at an-other opposite end to an outlet portion having a lon-gitudinal axis disposed on an outlet plane, said inlet portion allowing said plasma beam contain-ing macro-particles to travel toward said interme-diate portion in an incident direction and said out-let portion allowing said plasma beam to travel from said intermediate portion in an emergent di-rection, said intermediate portion being configured to deviate the incident direction to the emergent direction at an angle of more than 90° and thereby remove macro-particles from said plasma beam as it passes through said intermediate portion, and wherein said inlet plane and outlet plane are dis-posed at an offset angle from each other.

— *of inventorship (Rule 4.17(iv))*

Published:

— *with international search report (Art. 21(3))*